



**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: Karola Richter et al.  
Serial No: 10/553,728 Art Unit: 1765  
Filing Date: October 14, 2005  
Title: SILICON SUBSTRATE COMPRISING POSITIVE ETCHING  
PROFILES WITH A DEFINED SLOPE ANGLE AND PRODUCTION  
METHOD  
Examiner: Patricia Ann George

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October 12, 2007

Attorney's Docket No.: HMP201A2

**AMENDMENT**

Hon. Commissioner of Patents and Trademarks  
P.O. Box 1450, Alexandria, VA 22313  
SIR:

This is in response to the Office Action mailed on September 24, 2007, and setting a shortened statutory period for response of thirty days to expire on October 24, 2007. Applicants petition that, if required, the time for response be extended and the corresponding fee be charged. The Commissioner is hereby authorized to charge any additional fees which may be required to Acct. No. 11-0224. Applicants further respectfully request that this response be accepted as a bona fide effort to meet any potential response requirements outstanding and due in the above captioned matter.

Please amend the application as follows: